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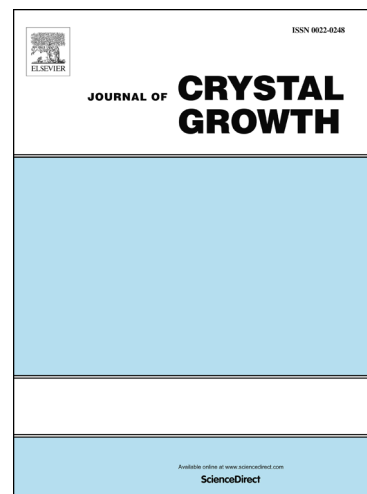
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**Impact of thickness on the structural properties
of high tin content GeSn layers**

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Abstract:

We have grown various thicknesses of GeSn layers in a 200 mm industrial Reduced Pressure - Chemical Vapor Deposition cluster tool using digermane (Ge_2H_6) and tin tetrachloride (SnCl_4). The growth pressure (100 Torr) and the $\text{F}(\text{Ge}_2\text{H}_6)/\text{F}(\text{SnCl}_4)$ mass-flow ratio were kept constant, and incorporation of tin in the range of 10% - 15% was achieved with a reduction in temperature: 325°C for 10% to 301°C for 15% of Sn. The layers were grown on 2.5 μm thick Ge Strain Relaxed Buffers, themselves on Si(001) substrates. We used X-Ray Diffraction, Atomic Force Microscopy, Raman spectroscopy and Scanning Electron Microscopy to measure the Sn concentration, the strain state, the surface morphology and thickness as a function of growth duration. A dramatic degradation of the film was seen when the Sn concentration and layer thickness were too high resulting in rough/milky surfaces and significant Sn segregation.

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